

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Brooks, et al.

Serial No.: 10/803,867

Confirmation No.: Unknown

Filed: March 18, 2004

For: Multi-Step Process for Etching Photomasks

Group Art Unit: Unknown

Examiner: Unknown

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING
37 CFR 1.8

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The Applicants, and the Attorney who signs below on the basis of the information supplied by the inventor and the information in his file, submit herewith patents, publications, or other information of which they are aware, which may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

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The patents and/or publications submitted herewith are set forth on the attached Form PTO-1449.

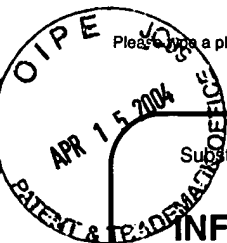
Applicants certify that all references submitted with this disclosure were first cited in a communication from a foreign patent office dated February 19, 2004, which communication is enclosed, not more than three months prior to the filing of this Information Disclosure Statement.

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Respectfully submitted,



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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Application Number	10/803,867
Filing Date	MARCH 18, 2004
First Named Inventor	BROOKS, ET AL.
Group Art Unit	UNKNOWN
Examiner Name	UNKNOWN
Attorney Docket Number	AMAT/7681/MASK/MASK-ETCH/ARNOLD S
Submission Date	April 12 2004

Sheet 1

of 1

NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
	A1	PCT Search Report for PCT/US03/11549, dated February 19, 2004 (AMAT/6991.PC)	
	A2	KWON, ET AL., "Loading Effect Parameters at Dry Etcher System and Their Analysis at Mask-to-Mask Loading and Within-Mask Loading" Proceedings of SPIE, Vol. 4562 (2002) pp. 79-87.	
	A3	FUJISAWA, ET AL. "Evaluation of NLD Mask Dry Etching System" SPIE Symposium on Photomask and X-Ray Technology VI, Yokohama, JAPAN, September (1999) Vol. 3748 pp. 147-152.	
	A4	RUHL, ET AL. "Chrome Dry Etch Process Characterization Using Surface Nano Profiling" Proceedings of SPIE, Vol. 4186 (2001) pp. 97-107.	
	A5	AOYAMA, ET AL. "Advanced Cr Dry Etching Process" SPIE Symposium on Photomask and X-Ray Technology VI, Yokohama, JAPAN, September (1999) SPIE, Vol. 3748 pp. 137-146.	

Examiner

Date Considered

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. 1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.

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